

METHOD AND DEVICE FOR EXPOSURE CONTROL,
METHOD AND DEVICE FOR EXPOSURE, AND
METHOD OF MANUFACTURE OF DEVICE

ABSTRACT

5 A method for exposure control comprising the steps of
measuring the change of the transmissivity or transmittance
for the light incident to the projection optical system
prior to the exposure operation effected by illuminating a
pattern on a reticle to form an image of the pattern on a
10 photosensitive wafer through the projection optical system,
storing the measured change of the transmissivity,
sequentially measuring the amount of the light incident to
the projection optical system during the exposure operation,
calculating the exposure light amount for the photosensitive
15 wafer from the exposure light amount based on the stored
change of the transmissivity, and integrating the exposure
from the start of the exposure operation to terminate the
exposure operation when the total exposure light amount has
reached a predetermined value. The total exposure light
20 amount for the wafer surface can be controlled even if the
transmissivity of the projection optical system fluctuates.